

The AIChE JOURNAL, a monthly publication of the American Institute of Chemical Engineers, is devoted to fundamental research and developments having immediate or potential value in chemical engineering.

EDITOR

Matthew V. Tirrell

MANAGING EDITOR

Haeja L. Han

COPY EDITOR

Arthur H. Baulch

EDITORIAL ASSISTANT

Karen M. Simpson

CONSULTING EDITORS

Richard Alkire

Electrochemical Engineering

Robert A. Brown

Computation

Mark E. Davis

Catalysis

Morton M. Denn

Materials

L. S. Fan

Particle Technology

Carol K. Hall

Thermodynamics

George E. Keller, II

Separations

Michael T. Klein

Reaction Engineering

Douglas A. Lauffenburger

Bioengineering

Julio M. Ottino

Transport Processes

Glen H. Pearson

Materials Processing

Ronald W. Rousseau

Crystallization

John Seinfeld

Environmental Engineering

Michael Shuler

Biochemical Engineering

George Stephanopoulos

Systems/Design

PRODUCTION DIRECTOR

Daniel Chillak

EDITOR-IN-CHIEF

Mark D. Rosenzweig

PUBLICATIONS DIRECTOR

Gary M. Rekstad

PROCESS CONTROL THEORY AND THE CPI...

IS THERE A BRIGHTER FUTURE SHINING THROUGH ALL THAT JARGON?

Despite its advances, process control theory has been slow to realize its full potential in the chemical processing industry. Control experts have "theorized" themselves out of the industrial loop. Control remains mostly an afterthought to process design. Yet safety and economics clearly demand more high-performance, non-linear control techniques in the CPI. Those are among the important issues addressed in the new volume of Chemical Process Control—CPCIV. This 700-page compendium contains 37 of the most significant papers from the Fourth International Conference on Chemical Process Control. It covers virtually every topic in the field that chemical engineers should know about. From inventory control in Japanese plants to modeling in neurobiology, these papers sum up five years of the very latest control applications from industry, academia, and government.

CHEMICAL PROCESS CONTROL—

CPCIV, 1991, edited by Yaman Arkun, Georgia Institute of Technology, and W. Harmon Ray, University of Wisconsin.

BE SURE TO ORDER YOUR COPY OF THIS IMPORTANT NEW REFERENCE!

Call: AIChE Publications Dept. (212) 705-7657.
Fax (212) 752-3294 for prices and ordering information.

AIChE Journal (ISSN 0001-1541) is published monthly by the American Institute of Chemical Engineers, 345 E. 47th St., New York, NY 10017. Manuscripts should be submitted to Editor Matthew V. Tirrell at the Dept. of Chemical Engineering and Materials Science, University of Minnesota, Minneapolis, MN 55455, phone (612) 625-5823, fax (612) 626-1686. The statements and opinions in the *AIChE Journal* are those of the contributors, and AIChE assumes no responsibility for them. Annual subscription rates: \$395 for nonmembers, \$60 for members, and \$30 for student members; outside U.S., add \$60 for postage. Single copies: \$40; outside U.S., add \$5 for postage. Second-class postage for domestic and air mail postage for foreign mailing paid at New York, NY and additional mailing offices. Copyright 1994 by the American Institute of Chemical Engineers. Subscribers are requested to give prompt notification of any change of address. Postmaster: Send changes of address to *AIChE Journal*, 345 East 47th St., New York, NY 10017. Authorization to photocopy items for internal or personal use, or the internal or personal use of specific clients, is granted by AIChE for libraries and other users registered with the Copyright Clearance Center (CCC) Transactional Reporting Service, provided that the \$3.50 per copy fee is paid directly to CCC, 21 Congress St., Salem, MA 01970. This consent does not extend to copying for general distribution, for advertising or promotional purposes, for inclusion in a publication, or for resale. Articles published before 1988 are subject to the same copyright conditions and the fee for each article is \$3.50. *AIChE Journal* fee code: 0001-1541/94 \$3.50.